

Attorney Docket:
033082 M 119



PATENT

H8/A
HCL
6-20-03

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

Hitoshi KATO, et al.

Serial No. : 10/066,627

Art Unit : 2822

Filed : February 6, 2002

Examiner : Maria F. Guerrero

For : A Precleaning Method of Precleaning a Silicon Nitride Film
Forming System (as amended)

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AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir :

A response to the Office Action dated March 13, 2003 (Paper No. 7) is due by June 13, 2003. Therefore, please accept this Amendment as timely filed and fully responsive.

In response to Paper No. 7, kindly amend the above-identified patent application as follows: